Special Issue

State-of-the-Art of Optical Micro/Nano-Metrology and Instrumentation

Message from the Guest Editors

State-of-the-art optical micro/nano-metrology in the manufacturing industry can be classified into two groups according to their main uses: those used for precision positioning, such as all kinds of optical sensors for linear and angular displacement measurement, and those used for quality assessment of products, such as interferometry, deflectometry, diffractometry and scatterometry for surface form or texture measurement, as well as optical coherence tomography for internal structure inspection. This Special Issue welcomes any papers about state-of-art optical micro/nano-metrology and instrumentation for precision positioning or quality assessment of products in manufacturing processes. The recent progress revealing novel optical measurement technologies and instrumentations in dealing with the new requirements and challenges with the advent of new processing technologies is also expected in this Special Issue.

Guest Editors

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As the world of science becomes ever more specialized, researchers may lose themselves in the deep forest of the ever increasing number of subfields being created. This open access journal Applied Sciences has been started to link these subfields, so researchers can cut through the forest and see the surrounding, or quite distant fields and subfields to help develop his/her own research even further with the aid of this multi-dimensional network.

Editor-in-Chief

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